

§413.70

SUBPART F—CHEMICAL ETCHING AND MILLING FACILITIES DISCHARGING 38,000 LITERS OR MORE PER DAY PSES LIMITATIONS (MG/SQ M-OPERATION)

Pollutant or pollutant property	Maximum for any 1 day	Average of daily values for 4 consecutive monitoring days shall not exceed
CN, T	74	39
Cu	176	105
Ni	160	100
Cr	273	156
Zn	164	102
Pb	23	16
Cd	47	29
Total metals	410	267

(e) For wastewater sources regulated under paragraph (c) of this section, the following optional control program may be elected by the source introducing treated process wastewater into a publicly owned treatment works with the concurrence of the control authority. These optional pollutant parameters are not eligible for allowance for removal achieved by the publicly owned treatment works under 40 CFR 403.7. In the absence of strong chelating agents, after reduction of hexavalent chromium wastes, and after neutralization using calcium oxide (or hydroxide) the following limitations shall apply:

SUBPART F—CHEMICAL ETCHING AND MILLING FACILITIES DISCHARGING 38,000 LITERS OR MORE PER DAY PSES LIMITATIONS (MG/L)

Pollutant or pollutant property	Maximum for any 1 day	Average of daily values for 4 consecutive monitoring days shall not exceed
CN, T	1.9	1.0
Pb	0.6	0.4
Cd	1.2	0.7
TSS	20.0	13.4
pH	(¹)	(¹)

¹ Within the range 7.5 to 10.0

(f) In addition to paragraphs (a) and (b) of this section, the following limitation shall apply for plants discharging less than 38,000 l (10,000 gal) per calendar day of electroplating process wastewater:

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Pollutant or pollutant property	Maximum for any 1 day
	Milligrams per liter (mg/l)
TTO	4.57

(g) In addition to paragraphs (a), (c), (d), and (e) of this section, the following limitation shall apply for plants discharging 38,000 l (10,000 gal) or more per calendar day of electroplating process wastewater:

Pollutant or pollutant property	Maximum for any 1 day
	Milligrams per liter (mg/l)
TTO	2.13

(h) In addition to paragraphs (a), (b), (c), (d), (e), (f), and (g) of this section, the following shall apply: An existing source submitting a certification in lieu of monitoring pursuant to §413.03 of this regulation must implement the toxic organic management plan approved by the control authority.

(Secs. 301, 304, 306, 307, 308, and 501 of the Clean Water Act (the Federal Water Pollution Control Act Amendments of 1972, 33 U.S.C. 1251 *et. seq.*, as amended by the Clean Water Act of 1977, Pub. L. 95-217))

[46 FR 9467, Jan. 28, 1981, as amended at 48 FR 32484, July 15, 1983; 48 FR 43681, Sept. 26, 1983]

Subpart G—Electroless Plating Subcategory

§413.70 Applicability: Description of the electroless plating subcategory.

The provisions of this subpart apply to discharges resulting from the electroless plating of a metallic layer on a metallic or nonmetallic substrate.

§413.71 Specialized definitions.

For the purpose of this subpart:
 (a) The term *sq m* ("sq. ft.") shall mean the area plated expressed in square meters (square feet).
 (b) The term *electroless plating* shall mean the deposition of conductive material from an autocatalytic plating solution without application of electrical current.